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(54) Title: METHOD FOR PRODUCTION OF WATER-SOLUBLE POROUS POLYMER AND WATER-SOLUBLE POROUS POLYMER

(57) Abstract: A method for efficient production of a water-soluble porous polymer and a water-soluble porous polymer excelling in solubility in water are provided. A method for the production of the polymer is characterized by the fact that an aqueous monomer solution containing an ethylenically unsaturated monomer is polymerized while it is containing bubbles therein. The method can simplify the drying and crushing steps and the water-soluble porous polymer consequently obtained excels in solubility in water.